Thick Tungsten and Rhenium coating by Chemical Vapor Deposition for fusion applications acerde X-ray tube focal spot **Problematics:** Use of Tungsten coatings in fusion and X-ray applications 0 3300-4200 W/mm² Tungsten-layer adhesion on Constraints for Tungsten coating in fusion **CVD-W characteristics** Rocket nozzle interior a carbon-rich surface High thermal load High purity 10 W/mm² Avoid cracking Particles bombardment (abrasion) High density Meteor entry High operating temperature (until 1500°C) High thermal conductivity 100-500 W/mm² Need of high thermal conductivity Fine control of deposited thickness (µm to mm) Same constraints for fusion Acerde uses Chemical Vapor Deposition to deposit an X-ray-emitting Brain surgery Fission reactor core 1-2 W/mm² tungsten layer on substrates in order to produce rotating X-ray anodes used Energy and X-ray applications in medical imaging devices. W-Re CVD coatings 0 Results: Carburization and barrier 1 CVD: 1 operation Experiments 0 WF_c $WF_{6(g)} + 3H_{2(g)} \rightarrow W_{(s)} + 6HF_{(g)}$ Tungsten-Rhenium alloy (1) Interface ReF₆ CVD Interface: Re barrier Н, It is well-known^(1,2,3) that a Rhenium-Multilaver Alternation of thin N₂ W-Re CVD multilayer system can act as a barrier W and Re layers system Re barrier Short annealing coating to prevent carbon migration. W Coating Graphite/CFC This multilayer system is deposited Alternation of substrate Graphite TEŠTS between the graphite substrate and thin Re interlayers Induction 1200/1400 °C and thick W layers heater the tungsten layer and included: Multilayer system before W-Re CVD Coating pump 1. A thick Rhenium layer called barrier carburization 2. An alternation of thin Tungsten-layers and Rhenium-layers. Results: Cracking resistance (2) 0 Carburization: The tungsten layer is deposited in Deposition erature increase Small grains During high temperature exposure, carbon diffusion from the several successive layers with rhenium Large cracks substrate to the W-layer leads to W_2C formation ^(4,5). interlayers. Between each W-layer, the Then, carbon atoms from the substrate react with W₂C phase to system is cooled to release thermal perature **Medium grains** stresses. form WC phase. Medium cracks – W-Re alloy – → Patents FR2962591 and FR1451695 Em More, the interface between each Large grains Carbide W₂C-Sectional view of a Small cracks layer will interfere to the cracks coating made of Carbide WC several W-layers with propagation and avoid the complete **Re-interlayers** cracking of the coating Re barrier Graphite Carburization of the multilayer Carburization of the multilayer 0 **Experiments for WEST:** system after annealing at 1250°C system after annealing at 1250°C -1h30 1h30 + 1400°C - 10h ACERDE realized tungsten \rightarrow Acerde studied carburization progression depending on the coatings on CFC tiles prototypes **Re-barrier thickness** for divertor that are currently 100µm at 1250°C (1h30) then 1200°C (10h) at 1250°C (1h30) then 1400°C (10h) 20 (mm C thickness (µm) being tested by the Design and 15 thickness Exploitation of Plasma Facing 10 *Components Group* (Cadarache) v,c 5 Ň CFC tile with W-coating for cross sectional view of the 0 W-coating on CFC tile divertor 5 15 5 15 25 35 ACERDE also realized W-deposition experiments on CFC bricks for Tokamak first wall Barrier thickness (um) Barrier thickness (µm) Carbide W₂C thickness depending on Carbide WC thickness depending on barrier thickness barrier thickness • Barrier thickness <20µm: after a short annealing at least at 1250°C, a controlled carbide layer is formed. This will reduce unwanted carburization during use at low temperature (1200°C) and high temperature (1400°C). • Barrier thickness >25 μ m: only W₂C at 1200°C is formed but there is uncontrolled carburization at 1400°C CFC brick with W-coating for first wall Conclusion Using HTCVD process developed by **Carburization:** ACERDE, W-layers and Re-interlayers can be -The best barrier thickness is between 20 and 25 μm; this allow first controlled carbide layer deposited in only one run formation which will prevent uncontrolled carbide formation during use at low temperature Cracking resistance:

 Depositing several successive layers with intercooling allows to reduce thermal stresses and control cracking

• High temperature deposition leads to less critical crack appearance

 Compared to requirements for fusion applications, HTCVD W-coating is a good alternative

(1) Liu et al. (2004) "High heat flux properties of pure tungsten and plasma sprayed tungsten coatings"; (2) Hirai et al. (2009) "Failure Modes of Vacuum Plasma Spray Tungsten Coatings Created on Carbon Fibre Composites under Thermal Load"; (3) Tamura et al. (2004) "Hightemperature properties of joint interface of VPS-tungsten coated CFC"; (4) Schmid et al. (2002) "Concentration dependent diffusion of carbon in tungsten"; (5) Luthin et al. (2000) "Carbon films and carbide formation on tungsten"

ACERDE SAS

Bâtiment CLEANSPACE 354 Voie Magellan Parc d'Activités ALPESPACE FR-73800 STE HELENE DU LAC



Standard : +33 (0)4 79 26 48 27 Fax : +33 (0)4 26 23 67 38 E-Mail : info@acerde.com Web : http://www.acerde.com

